

L Number	Hits	Search T xt	DB	Time stamp
1	586	438/669.ccls.	USPAT	2004/07/01 19:52
2	152	438/671.ccls.	USPAT	2004/07/01 19:53
3	640	438/720.ccls.	USPAT	2004/07/01 19:53
4	574	438/725.ccls.	USPAT	2004/07/01 19:53
5	368	438/734.ccls.	USPAT	2004/07/01 19:53
6	170	438/735.ccls.	USPAT	2004/07/01 19:53
7	145	438/736.ccls.	USPAT	2004/07/01 19:53
8	125	438/737.ccls.	USPAT	2004/07/01 19:53
9	221	438/742.ccls.	USPAT	2004/07/01 19:59
10	163	438/942.ccls.	USPAT	2004/07/01 19:54
11	232	438/945.ccls.	USPAT	2004/07/01 19:54
12	22	438/946.ccls.	USPAT	2004/07/01 19:54
13	226	438/947.ccls.	USPAT	2004/07/01 19:54
14	2835	430/5.ccls.	USPAT	2004/07/01 19:55
15	2	matsunuma-takeshi\$.in.	USPAT	2004/07/01 19:55
16	5	matsunuma-takeshi\$.in.	US-PGPUB	2004/07/01 19:55
17	0	matsunuma-takeshi\$.in.	EPO; JPO; DERWENT; IBM_TDB	2004/07/01 19:56
18	60810	(mask\$6 and (resist photoresist) and pattern\$6)	USPAT	2004/07/01 20:01
19	50937	((mask\$6 and (resist photoresist) and pattern\$6)) and (shrink\$6 shrunk reduc\$6)	USPAT	2004/07/01 19:59
20	245	((((mask\$6 and (resist photoresist) and pattern\$6)) and (shrink\$6 shrunk reduc\$6)) and ((ruthenium "ru") same mask\$6)	USPAT	2004/07/01 20:01
21	709	438/710.ccls.	USPAT	2004/07/01 19:59
22	16815	((((mask\$6 and (resist photoresist) and pattern\$6)) and (shrink\$6 shrunk reduc\$6)) and ((shrink\$6 shrunk redu \$6) sam (mask\$6))	USPAT	2004/07/01 20:03
23	7030	(((((mask\$6 and (resist ph t resist) and patt rn\$6)) and (shrink\$6 shrunk r duc\$6)) and ((shrink\$6 shrunk reduc\$6) same (mask\$6))) and ((m tal) same (mask\$6))	USPAT	2004/07/01 20:00

24	1125	(((mask\$6 and (resist ph t r sist) and patt m\$6)) and (shrink\$6 shrunk reduc\$6)) and ((shrink\$6 shrunk r duc\$6) same (mask\$6))) and ((m tal) same (mask\$6))) and ((m tal) adj2 (mask\$6))	USPAT	2004/07/01 20:02
25	22742	(mask\$6 and (resist ph toresist) and pattern\$6)	US-PGPUB	2004/07/01 20:01
26	183	((mask\$6 and (resist photoresist) and pattern\$6)) and ((ruthenium "ru") same mask\$6)	US-PGPUB	2004/07/01 20:02
27	29143	(mask\$6 and (resist photoresist) and pattern\$6)	EPO; JPO; DERWENT; IBM_TDB	2004/07/01 20:01
28	4928	((mask\$6 and (resist photoresist) and pattern\$6)) and ((metal) same (mask\$6))	EPO; JPO; DERWENT; IBM_TDB	2004/07/01 20:02
29	12	(((mask\$6 and (resist photoresist) and pattern\$6)) and ((metal) same (mask\$6))) and ((ruthenium "ru") same mask\$6)	EPO; JPO; DERWENT; IBM_TDB	2004/07/01 20:02
30	478	(((mask\$6 and (resist photoresist) and pattern\$6)) and ((metal) same (mask\$6))) and ((shrink\$6 shrunk reduc\$6) same (mask\$6))	EPO; JPO; DERWENT; IBM_TDB	2004/07/01 20:03